

INFORMATION DISCLOSURE CITATION IN AN OPIE APPLICATION

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 APPLICANT
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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Codez (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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		JP 08-204484	07/22/1994	HITACHI LTD		Japanese (w/ English Abstract)	
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		Mitsue Takahashi et al., "ANALYSIS AND IMPROVEMENT OF RETENTION TIME OF MEMORIZED STATE OF METAL-FERROELECTRIC-INSULATOR-SEMICONDUCTOR STRUCTURE FOR FERROELECTRIC GATE FET MEMORY", The Japan Society of Applied Physics, January 5, 2001, pp. 2923-2927

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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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